

CLAIMS

WHAT IS CLAIMED IS:

- 0975050-000404
- 1 1. A lithographic system for an integrated circuit fabrication
2 process, the lithographic system comprising:
3 a computer; and
4 a configurable mask or reticle coupled to the computer,
5 wherein the configurable mask or reticle allows light to be transmitted in a
6 pattern controlled by a control signal from the computer.
 - 1 2. The lithographic system of claim 1, wherein the configurable
2 mask or reticle is an LCD or LED matrix.
 - 1 3. The lithographic system of claim 1 further comprising:
2 a database for providing image information associated with a
3 device to be patterned on a wafer, the computer using the image
4 information to generate the control signal.
 - 1 4. The lithographic system of claim 3, wherein the database is
2 stored on a storage media.
 - 1 5. The lithographic system of claim 3, wherein the image
2 information is related to transistor structures.
 - 1 6. The lithographic system of claim 1, wherein the control
2 signal is a video signal.
 - 1 7. A method of manufacturing an integrated circuit, the method
2 comprising:
- SUB B1

3 providing a pattern of radiation via an LCD or LED assembly;
4 and
5 performing a semiconductor fabrication process in
6 accordance with the pattern of radiation.

1 8. The method of claim 7, further comprising:
2 providing a second pattern of radiation via the LCD or LED
3 assembly; and
4 performing a second semiconductor fabrication process in
5 accordance with the second pattern of radiation.

1 9. The method of claim 7, wherein the pattern is provided to a
2 wafer in a step and repeat process.

1 10. The method of claim 7, wherein the pattern is representative
2 of a metal layer associated with the integrated circuit.

1 11. The method of claim 7, wherein the pattern is representative
2 of a structure associated with a transistor for the integrated circuit.

1 SUB 12. The method of claim 7, wherein a representation of the
2 B2 pattern is stored electronically.

1 13. The method of claim 7, wherein the integrated circuit is an
2 ASIC.

1 14. The method of claim 7, wherein the pattern is provided via
2 the LCD assembly.

1 15. A pattern generator for an integrated circuit fabrication
2 system, the pattern generator comprising:

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3 means for providing a pattern of light; and
4 means for controlling the means for providing, wherein the
5 means for controlling selects the pattern.

1 16. The pattern generator of claim 15, further comprising:
2 means for providing a light through the means for providing a
3 pattern.

1 17. The pattern generator of claim 16, further comprising:
2 means for focusing the light on a wafer.

1 18. The pattern generator of claim 15, further comprising:
2 means for storing elements, wherein the means for
3 controlling creates a control signal representative of the pattern in
4 response to the elements.

1 19. The pattern generator of claim 15, wherein the means for
2 controlling includes a workstation executing a software program.

1 20. The pattern generator of claim 19, wherein the means for
2 providing a pattern includes liquid crystals.

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